

MARKED-UP COPY OF AMENDMENTS

IN RE APPLICATION OF

HIROSHI IKEDA ET AL

SERIAL NO: 09/463,961

FILED: MAY 25, 2000



: EXAMINER: VANOVY, T.

: GROUP ART UNIT: 1754

: RCE FILED: HEREWITH

FOR: METHOD AND APPARATUS  
FOR PROCESSING EXHAUST  
GAS OF SEMICONDUCTOR  
FABRICATION

PRELIMINARY AMENDMENT AND REMARKS

ASSISTANT COMMISSIONER FOR PATENTS  
WASHINGTON, D.C. 20231

SIR:

Further to the Notice of Appeal filed May 21, 2002, and in further response to the Final Rejection dated November 21, 2001, the period for response having been extended to August 21, 2002, by a petition for extension of time filed herewith, please amend the application identified above as follows (marked-up copy of amendments):

IN THE CLAIMS

Please amend Claim 1 as follows:

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1. (Two Times Amended) A process for treating exhaust gases, the process comprising

a step of providing an aeration stirring tank having a stirring device comprising a motor, a shaft rotatably connected to the motor, and a blade attached to the shaft;

a step of introducing exhaust gases into an aqueous alkaline liquid in said aeration stirring tank while stirring the aqueous alkaline liquid thereby turning the exhaust gases into fine foam by the shear force of the stirring blade to disperse the liquid; and

a step of further removing harmful gases from the gases discharged from the aeration stirring tank.